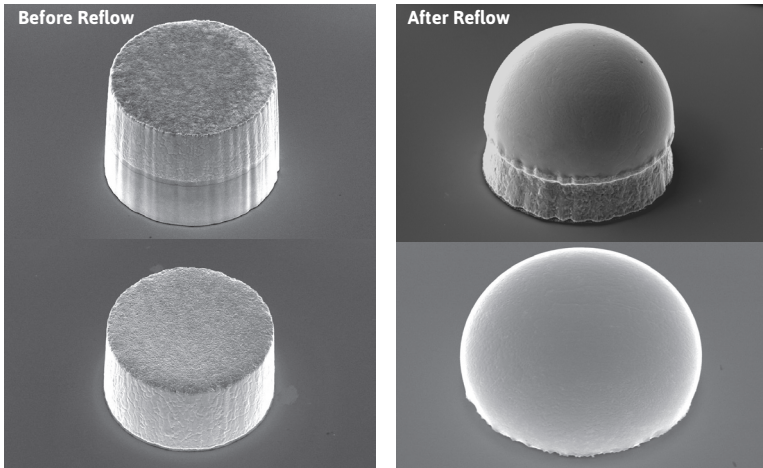


# MICROFAB<sup>®</sup> TS-650

FOR THE MOST CRITICAL INTERFACE BETWEEN WLP AND SUBSTRATE

**Introducing MICROFAB<sup>®</sup> TS-650:** The premier tin-silver bump metallization from the market leader in copper pillar for FO-WLP



## KEY FEATURES

- Foaming-free and stable electrolyte
- Environmentally-friendly lead-free process
- High deposition rates
- For bumping and capping applications
- Smooth and uniform deposit
- Tunable Ag composition
- Excellent post reflow WID bump uniformity
- Horizontal or vertical equipment

